

FORM PTO-1449

Atty. Docket No.

Appln. No.

XA-7709G

10/721,425

## LIST OF DOCUMENTS CITED BY APPLICANT

Applicant

Kenji NISHI

Filing Date

November 26, 2003

Group

285)

## U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub-class	Filing Date
Pt	AA	4,748,478	5/31/88	Suwa et al.	355	53	
	AB	4,829,193	5/9/89	Nishi	250	548	
	AC	4,880,310	11/14/89	Nishi	356	401	
	AD	4,902,900	2/20/90	Kamiya et al.	250	548	
	AE	4,941,093	7/10/90	Marshall et al.	364	413.01	
	AF	4,962,318	10/9/90	Nishi	250	548	
	AG	5,084,729	1/28/92	Yakubo et al.	355	74	
	AH	5,309,198	5/3/94	Nakagawa	355	67	
	AI	5,912,727	6/15/99	Kawai	355	67	
Pt	AJ	RE37,391	9/25/01	Nishi	355	53	

## FOREIGN PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Country	Class	Sub-class	Translation
Pt	AL	2-65222	3/5/90	Japan			Abstract
Pt	AM	2-116115	4/27/90	Japan			Abstract

## OTHER (including author, title, date, pertinent pages, etc.)

Pt	AQ	Pfeiffer, H., "Advanced E-Beam System for Manufacturing", <u>SPIE</u> , Vol. 1671, 1992, pp. 100-110.					
Pt	AR	Haytcher, E. et al., "Finite Element Analysis of Dynamic Thermal Distortions of an X-ray Mask for Synchrotron Radiation Lithography", <u>SPIE</u> , Vol. 1671, 1992, pp. 347-356.					
Pt	AS	Chen, G. et al., "Implementation of Two-State Alignment System into CXrL Aligner", <u>SPIE</u> , Vol. 1671, 1992, pp. 471-486.					
Pt	AT	Hohn, F. et al., "Electron Beam Lithography, Directions in Direct Write and Mask Making", <u>SPIE</u> , Vol. 1263, 1990, pp. 152-163.					
Pt		Nakayama, Y. et al. "Highly Accurate Calibration Method of Electron-beam Cell Projection Lithography", <u>SPIE</u> , Vol. 1924, 1993, pp. 183-192.					
Pt		Franco, E. et al., "What is Required for Collimated Point-Source X-ray Lithography to Achieve an Economically Viable Throughput?", <u>SPIE</u> , Vol. 1924, 1993, pp. 371-380.					

Examiner

Date Considered

11-7-04

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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Examiner Initial		Document Number	Date	Name	Class	Sub-class	Filing Date
PA	BA	4,191,466	03/1980	Gandini	355	53	
	BB	4,030,825	06/1977	Ghougasian	355	71	
	BC	5,656,402	08/1995	Kasuga	430	22	
	BD	4,918,320	03/1988	Hamasaki et al.	250	548	
	BE	5,677,754	06/1995	Makinouchi	355	53	
	BF	4,924,257	05/1990	Jain	355	53	
	BG	4,747,678	05/1988	Shafer et al.	350	505	
	BH	5,105,075	04/1992	Ohta et al.	355	53	
	BI	5,473,410	12/1995	Nishi	355	53	
PA	BJ	5,214,489	05/1993	Mizutani et al.	356	363	
	BK						
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Examiner Initial		Document Number	Date	Country	Class	Sub-class	Translation
PA	BL	63-128713	06/01/88	Japan			Yes
	BM						
	BN						
<b>OTHER</b> (including author, title, date, pertinent pages, etc.)							
	BO						
	BP						
	BQ						
<b>Examiner</b> R. S. [Signature]				<b>Date Considered</b> 11-7-04			
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Examiner Initial		Document Number	Date	Name	Class	Sub-class	Filing Date
P	CA	5,661,546	09/1994	Taniguchi	355	53	
↑	CB	5,365,342	11/1994	Ayata et al.	356	401	
	CC	6,018,395	01/2000	Mori et al.	356	401	
	CD	5,835,196	11/1998	Jackson	355	53	
	CE	5,854,671	12/1998	Nishi	355	53	
	CF	6,072,184	06/2000	Okino et al.	250	492.2	
	CG	6,118,517	09/2000	Sasaki et al.	355	53	
	CH	5,289,231	02/1994	Magome et al.	355	53	
	CI	4,699,515	10/1987	Tanimoto	356	40	
↓	CJ	5,801,832	9/1998	Van Den Brink	365	500	
P	CK	6,249,335	6/2001	Hirukawa et al.	355	53	
<b>FOREIGN PATENT DOCUMENTS</b>							
Examiner Initial		Document Number	Date	Country	Class	Sub-class	Translation
	CL						
	CM						
	CN						
<b>OTHER</b> (including author, title, date, pertinent pages, etc.)							
	CO						
	CP						
	CQ						
<b>Examiner</b> R. J. [Signature]				<b>Date Considered</b> 11-7-04			
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PA	DA	3,538,828	11/10/70	Genovese	95	18	
	DB	4,659,225	4/21/87	Takahashi	356	358	
	DC	4,748,478	5/31/88	Suwa et al.	355	53	
	DD	4,749,867	6/7/88	Matsushita et al.	250	442.1	
	DE	4,822,975	4/18/89	Torigoe	219	121.85	
	DF	5,004,348	4/2/91	Magome	356	401	
	DG	5,187,519	2/16/93	Takabayashi et al.	355	53	
	DH	5,506,684	4/9/96	Ota et al.	356	401	
	DI	5,767,948	6/16/98	Loopstra et al.	355	53	
PA	DJ	5,796,469	8/18/98	Ebinuma	355	53	
	DK						
<b>FOREIGN PATENT DOCUMENTS</b>							
Examiner Initial		Document Number	Date	Country	Class	Sub-class	Translation
PA	DL	4-235558	8/24/92	JAPAN (Laid-Open)			Yes
	DM						
	DN						
<b>OTHER</b> (including author, title, date, pertinent pages, etc.)							
	DO						
	DP						
	DQ						
<b>Examiner</b> R. J. F. H.				<b>Date Considered</b> 11-7-04			
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PA	AA	5,194,893	03/1993	Nishi	355	53		
	AB	5,281,996	01/1994	Bruning et al.	355	77		
	AC	5,227,839	07/1993	Allen	355	53		
	AD	3,819,265	06/1974	Feldman et al.	355	51		
	AE	4,953,960	09/1990	Williamson	350	442		
	AF	5,089,913	02/1992	Singh et al.	359	727		
	AG	5,238,870	08/1993	Tanaka	437	173		
	AH	5,285,236	02/1994	Jain	355	53		
	AI	5,291,240	03/1994	Jain	355	53		
	AJ	5,912,727	06/1999	Kawai	355	67		
PA	AK	4,734,746	03/1988	Ushida et al.	355	53		
<b>FOREIGN PATENT DOCUMENTS</b>								
Examiner Initial		Document Number	Date	Country	Class	Sub-class	Translation	
PA	AL	2-229423	09/1990	JAPAN (Laid-Open)			No	
PA	AM	4-277612	02/1992	JAPAN			No	
PA	AN	1-91419	04/1989	JAPAN			Yes	
<b>OTHER</b> (including author, title, date, pertinent pages, etc.)								
PA	AO	Tracy et al., "Exposure Dose Control Techniques for Excimer Laser Lithography" in SPIE Vol. 922 <u>Optical/Laser Microlithography</u> , 1988, pp. 437-443.						
PA	AP	Rominger, "Seamless Stitching for Large Area Integrated Circuit Manufacturing" in SPIE Vol. 922 <u>Optical/Laser Microlithography</u> , 1988, pp. 188-193.						
PA	AQ	Buckley et al., "Step and scan: A system overview of a new lithography tool" in SPIE Vol. 1088 <u>Optical/Laser Microlithography II</u> , 1989.						
Examiner <i>R. J. Fule</i>				Date Considered 11-3-04				
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